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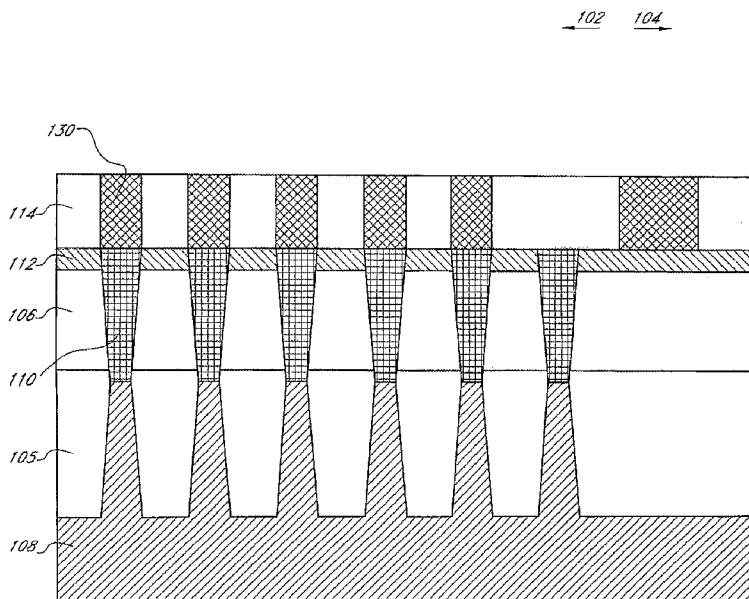
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(54) Title: INTEGRATED CIRCUIT FABRICATION



(57) Abstract: A method for defining patterns in an integrated circuit (100) comprises defining a plurality of features in a first photoresist layer using photolithography over a first region (102) of a substrate (108). The method further comprises using pitch multiplication to produce at least two features (120) in a lower masking layer (116) for each feature in the photoresist layer. The features in the lower masking layer (116) include looped ends (124). The method further comprises covering with a second photore-sist layer (126) a second region (104) of the substrate (108) including the looped ends (124) in the lower masking layer (116). The method further comprises etching a pattern of trenches in the substrate (108) through the features in the lower masking layer without etching in the second region (104). The trenches have a trench width.

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B. FIELDS SEARCHED

Minimum documentation searched (classification system followed by classification symbols)
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Documentation searched other than minimum documentation to the extent that such documents are included in the fields searched

Electronic data base consulted during the international search (name of data base and, where practical, search terms used)

EPO-Internal, WPI Data

C. DOCUMENTS CONSIDERED TO BE RELEVANT

Category*	Citation of document, with indication, where appropriate, of the relevant passages	Relevant to claim No.
A	US 5 328 810 A (LOWREY TYLER A [US] ET AL) 12 July 1994 (1994-07-12) cited in the application the whole document	1-73
A	US 6 010 946 A (HISAMUNE YOSIAKI [JP] ET AL) 4 January 2000 (2000-01-04) column 8, line 14 - column 9, line 26; figures 5A-6D	1-73
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A	US 2003/230234 A1 (NAM DONG-SEOK [KR] ET AL) 18 December 2003 (2003-12-18) the whole document	1-73

 Further documents are listed in the continuation of Box C. See patent family annex.

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Information on patent family members

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Patent document cited in search report	Publication date	Publication date	Patent family member(s)	Publication date
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